

# 2011 International Conference on Planarization/CMP Technology (2011 ICPT)

2011



International Conference on Planarization/CMP Technology

**November 9-11, 2011**

**COEX, Seoul, KOREA**

# 2011 International Conference on Planarization/CMP Technology (ICPT 2011)

◆ **Date** : November 9-11, 2011. Nov. 12: Social Program

◆ **Place** : COEX, Seoul, Korea

◆ **Local Organizing Committee**

**Chair**: Jin-Goo Park (Hanyang University)

**Co-Chairs**: Hae-Do Jeong (PNU), Tea-Sung Kim (SKKU)

◆ **Subjects of Interest**

- Copper/low-k CMP processes and control
- CMP process integration issues and reliability
- CMP defects
- CMP consumable (pads, slurries)
- CMP modeling, simulation and theory
- Metrology, characterization and test
- Advances in ECD/ECP/ECMP processes and tools
- CMP in emerging technologies
- Dielectric/STI CMP processes and control
- Corrosion control during CMP process
- Post CMP cleaning
- CMP equipment and metrology
- Chemical and physical mechanisms of CMP
- Advanced CMP process control techniques
- Low-shear CMP

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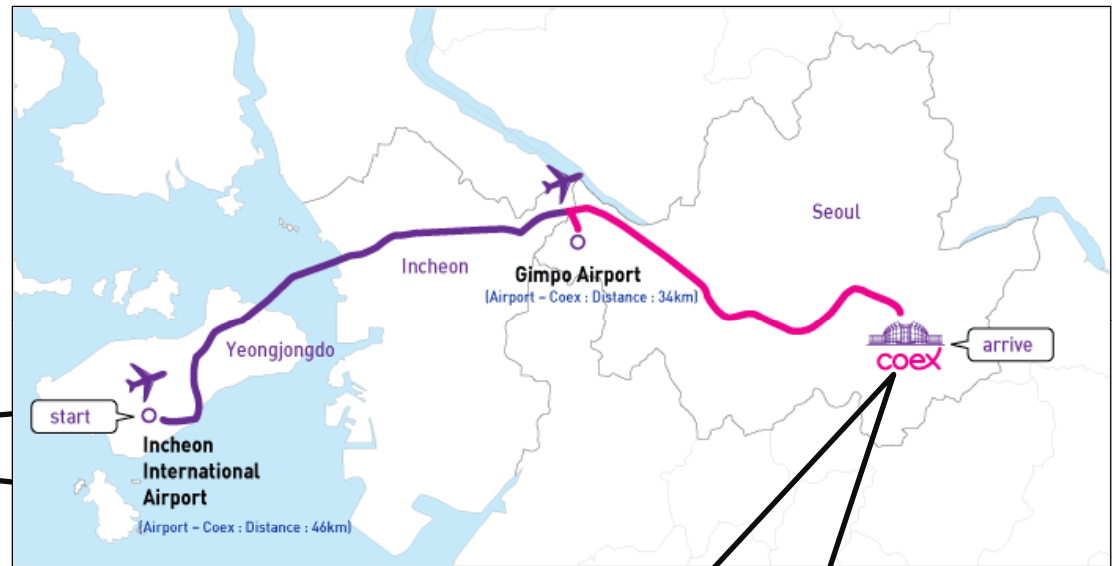
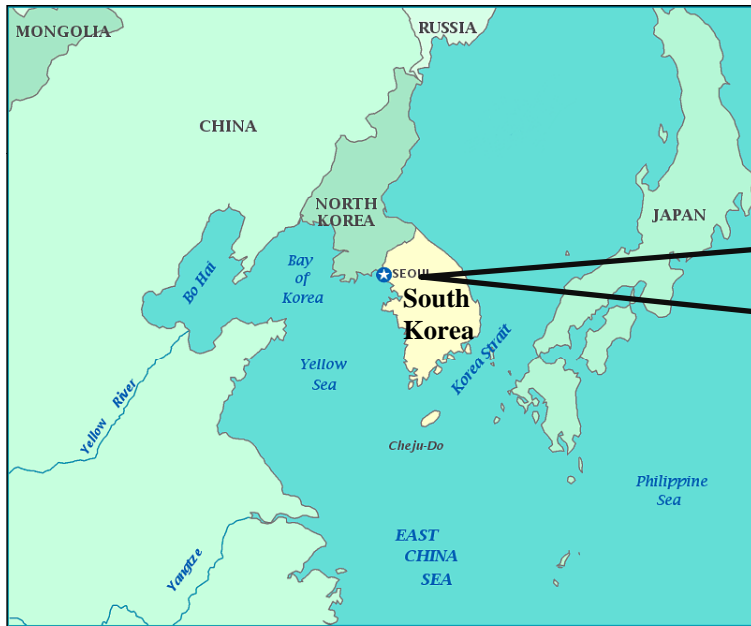


## THE SEOUL SUMMIT 2010

Shared Growth Beyond Crisis



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